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APPLICATION NO.	FILING	DATE	FIRST NAMED INVENTOR	ATTORNEY DOCKET NO.	CONFIRMATION NO.	
10/678,699	10/678,699 10/03/2003		Wen Chin Lin	24061.32	9863	
42717	7590	07/20/2006		ÉXAMINER		
	AND BOON	NGUYEN,	NGUYEN, DANG T			
901 MAIN STREET, SUITE 3100 DALLAS, TX 75202				ART UNIT	PAPER NUMBER	
,				2824		
				DATE MAILED: 07/20/2000	DATE MAILED: 07/20/2006	

Please find below and/or attached an Office communication concerning this application or proceeding.

PTO-90C (Rev. 10/03)

		Application No.	Applicant(s)			
Office Action Summary		10/678,699	LIN ET AL.			
		Examiner	Art Unit			
		Dang T. Nguyen	2824			
The MAILING DATE of this communication appears on the cover sheet with the correspondence address Period for Reply						
WHIC - Exter after - If NO - Failu Any r	CRTENED STATUTORY PERIOD FOR REPLY CHEVER IS LONGER, FROM THE MAILING DAISIONS of time may be available under the provisions of 37 CFR 1.13 SIX (6) MONTHS from the mailing date of this communication. Period for reply is specified above, the maximum statutory period we to reply within the set or extended period for reply will, by statute, eply received by the Office later than three months after the mailing and patent term adjustment. See 37 CFR 1.704(b).	ATE OF THIS COMMUNICATION  16(a). In no event, however, may a reply be tim  rill apply and will expire SIX (6) MONTHS from  cause the application to become ABANDONED	I. tely filed the mailing date of this communication. (35 U.S.C. § 133).			
Status						
2a)□	Responsive to communication(s) filed on 10 Minus action is FINAL. 2b) ☑ This Since this application is in condition for alloward closed in accordance with the practice under E	action is non-final. nce except for formal matters, pro				
Disposition of Claims /						
5) □ 6) ⊠ 7) □ 8) □ Applicati 9) □ 10) ⊠	Claim(s) 11-18 and 20-32 is/are pending in the 4a) Of the above claim(s) is/are withdraw Claim(s) is/are allowed.  Claim(s) 11-18 and 20-32 is/are rejected.  Claim(s) is/are objected to.  Claim(s) is/are objected to.  Claim(s) are subject to restriction and/or on Papers  The specification is objected to by the Examine The drawing(s) filed on 03 October 2003 is/are:  Applicant may not request that any objection to the or Replacement drawing sheet(s) including the correction of the oath or declaration is objected to by the Examine contents of the oath or declaration is objected to by the Examine contents of the oath or declaration is objected to by the Examine contents of the oath or declaration is objected to by the Examine contents of the oath or declaration is objected to by the Examine contents of the oath or declaration is objected to by the Examine contents of the oath or declaration is objected to by the Examine contents of the oath or declaration is objected to by the Examine contents of the oath or declaration is objected to by the Examine contents of the oath or declaration is objected to by the Examine contents of the oath or declaration is objected to by the Examine contents of the oath or declaration is objected to by the Examine contents of the oath or declaration is objected to by the Examine contents of the oath or declaration is objected to by the Examine contents of the oath or declaration is objected to by the Examine contents of the oath or declaration is objected to by the Examine contents of the oath or declaration is objected to by the Examine contents of the oath or declaration is objected to by the Examine contents of the oath or declaration is objected to be objected to by the Examine contents of the oath of the oath or declaration is objected to be obj	vn from consideration.  r election requirement.  r.  a)⊠ accepted or b)□ objected drawing(s) be held in abeyance. See ion is required if the drawing(s) is obj	e 37 CFR 1.85(a). lected to. See 37 CFR 1.121(d).			
Priority (	inder 35 U.S.C. & 119					
Priority under 35 U.S.C. § 119  12) Acknowledgment is made of a claim for foreign priority under 35 U.S.C. § 119(a)-(d) or (f).  a) All b) Some colonomer Some Some Some Some Some Some Some Some						
2) Notice	t(s) e of References Cited (PTO-892) e of Draftsperson's Patent Drawing Review (PTO-948) mation Disclosure Statement(s) (PTO-1449 or PTO/SB/08) r No(s)/Mail Date 3/10/06.	4)  Interview Summary Paper No(s)/Mail Da 5)  Notice of Informal P 6)  Other: <u>Search histo</u>	ate latent Application (PTO-152)			

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### **DETAILED ACTION**

1. This office action is in response to Request for Continued Examination (RCE) received on March 10, 2006. Claims 18 and 26 have been amended. Claims 1 – 10 and 19 have been cancelled. Claims 11 – 18 and 20 - 32 are pending on this application. Claims 11, 18 and 27 are independent claims.

## Information Disclosure Statement

2. Acknowledgment is made of applicant's Information Disclosure Statement (IDS) Form PTO-1449, filed on 03/10/06, and the cited information has been considered.

## Claim Rejections - 35 USC § 102

3. The following is a quotation of the appropriate paragraphs of 35 U.S.C. 102 that form the basis for the rejections under this section made in this Office action:

A person shall be entitled to a patent unless -

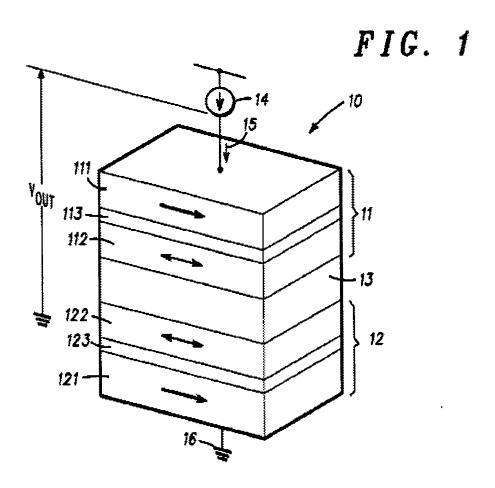
(b) the invention was patented or described in a printed publication in this or a foreign country or in public use or on sale in this country, more than one year prior to the date of application for patent in the United States.

Claims 11-13, 16-18, 20 and 24-32 are rejected under 35 U.S.C. 102(b) as being anticipated by Zhu, Patent No. 5,930,164 B1 – Date of Patent: Feb. 26, 1998.

Regarding independent claim 11, Fig. 1 of Zhu discloses a magnetic memory cell comprising a switching element and a magnetic tunnel junction (MTJ) configuration comprising:

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a first MTJ device [11] including a first free layer [112], a first tunneling barrier [113], and a first pinned layer [111];

a second MTJ device including a second free layer [122], a second tunneling barrier [123], and a second pinned layer [121];

a first conductor [13] connecting the first [11] and second [12] MTJ devices; wherein a first magneto-resistance of the first MTJ device is different from a second

magneto-resistance of the second MTJ device (Col. 2 line 53 – Col. 3 line 2).

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Regarding dependent claim 12, Zhu discloses the memory cell of claim 11 wherein the second magneto-resistance is twice of the first magnetic resistance (Col. 6 lines 46-47).

Regarding dependent claim 13, Fig. 1 of Zhu discloses the memory cell of claim 11 wherein the second MTJ device includes an anti-ferromagnetic material and wherein the first free layer is connected to the anti-ferromagnetic material through the first conductor (Col. 1 lines 31-34).

Regarding dependent claim 16, Fig. 1 of Zhu discloses the memory cell of claim 11 wherein the first tunneling barrier [113] is comprised of a different material than the second tunneling barrier [123] (Col. 1 line 66 – Col. 2 line 2).

Regarding dependent claim 17, Fig. 1 of Zhu discloses the memory cell of claim 11 wherein the first tunneling barrier [113] is formed from a different processing recipe than the second tunneling layer [123] (Col. 2 line 60 - 66).

**Regarding independent claim 18**, Figs. 1 - 3 of Zhu disclose an integrated circuit comprising:

an input/output section (Fig. 3 [33]);

a plurality of logic circuits (Fig. 3 [W1, W2]) connected to the input/output section (Col. 4 lines 65-67); and

a plurality of magnetic memory cells (Fig. 3 [34 and 35]) connected to the logic circuits (Fig. 3 [W1, W2]) and (Col. 4 lines 65-67), the magnetic memory cells (Fig. 3 [34 and 35]) including a transistor (Fig. 3 [37 – 39]) and a storage structure (see Fig. 1) including:

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a first MTJ device [11] including a first free layer [112], a first tunneling barrier [113], and a first pinned layer [111];

a second MTJ device including a second free layer [122], a second tunneling barrier [123], and a second pinned layer [121]; and

a first conductor [13] connected to configure the first [11] and second [12] magnetic junction devices in parallel (Col. 5 line 62);

wherein a first magneto-resistance ratio of the first MTJ device is different from a second magneto-resistance ratio of the second MTJ device (Col. 2 line 53 – Col. 3 line 2).

Regarding dependent claim 20, Fig. 1 of Zhu discloses the integrated circuit of claim 18 wherein the second magnetic junction device [12] includes an anti-ferromagnetic material [121] (Col. 6 lines 40-41) and wherein the first free layer [112] is connected to the anti-ferromagnetic material [121] through the first conductor [13].

Regarding dependent claim 24, Fig. 1 of Zhu discloses the memory cell of claim 18 wherein the first tunneling barrier [113] is comprised of a different material than the second tunneling barrier [123] (Col. 1 line 66 – Col. 2 line 2).

Regarding dependent claim 25, Fig. 1 of Zhu discloses the memory cell of claim 18 wherein the first tunneling barrier [113] is formed from a different processing recipe than the second tunneling layer [123] (Col. 2 line 60 - 66).

Regarding dependent claim 26, Fig. 1 of Zhu discloses the integrated circuit of claim 18 wherein the first magneto-resistance ratio of the first tunneling barrier [113] is 50-60% (Zhu discloses a first barrier [113] has a thickness of 22-30 Angstrom) and the second magneto-resistance ratio of the second tunneling barrier [123] is 20-30% (Zhu

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discloses a second barrier [123] has a thickness of 15-22 Angstrom) (Col. 2 lines 50-51 and 60-61, similar to 50% different ratio between first and second magnetoresistance).

**Regarding independent claim 27**, Fig. 1 of Zhu discloses an apparatus, comprising:

a first magnetic tunnel junction [11] having a first magneto-resistance ratio (Col. 2 lines 50-51, a first barrier [113] has a thickness of 22-30 Angstrom); and a second magnetic tunnel junction [12] having a second magneto-resistance ratio (Col. 2 lines 60-61, a second barrier [123] has a thickness of 15-22 Angstrom), wherein: the first and second magnetic tunnel junctions [11 and 12] are electrically connected; and the first magneto-resistance ratio and the second magneto-resistance ratio are substantially different (the two barrier layers in the memory cells have different thickness which produce a different magneto-resistance ratio, col. 1 line 66 – col. 2 line 2 and col. 2 line 50 – col. 3 line 2).

Regarding dependent claim 28, Zhu discloses the apparatus of claim 27 wherein the first magneto-resistance ratio is about 50% of the second magneto-resistance ratio (Col. 2 lines 50-51 and 60-61).

Regarding dependent claim 29, Fig. 1 of Zhu discloses the apparatus of claim 27 wherein:

the first magnetic tunnel junction [11] has a first tunnel barrier [113] having a first composition;

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the second magnetic tunnel junction [12] has a second tunnel barrier [123] having a second composition; and the first and second compositions are different (Col. 1 line 66 – col. 2 line 2).

Regarding dependent claim 30, Fig. 1 of Zhu discloses the apparatus of claim 27 wherein a first magnetic layer [112] of the first magnetic tunnel junction [11] is located between the second magnetic tunnel junction [12] and a second magnetic layer [113] of the first magnetic tunnel junction [11].

Regarding dependent claim 31, Fig. 1 of Zhu discloses the apparatus of claim 27 wherein no magnetic layer [13] of the first magnetic tunnel junction [11] is located between the second magnetic tunnel junction [12] and any other magnetic layer [112] of the first magnetic tunnel junction [11].

**Regarding dependent claim 32**, Fig. 1 of Zhu discloses the apparatus of claim 27 wherein:

the first magnetic tunnel junction [11] comprises a pinned layer 111], a first free layer [112], and a first tunnel barrier [113] located between the pinned layer [111] and the first free layer [112]; and

the second magnetic tunnel junction [12] comprises the first free layer [112], a second free layer [122], and a second tunnel barrier [123] located between the first and second free layers [112 and 122].

## Claim Rejections - 35 USC § 103

4. The following is a quotation of 35 U.S.C. 103(a) which forms the basis for all

obviousness rejections set forth in this Office action:

(a) A patent may not be obtained though the invention is not identically disclosed or described as set forth in section 102 of this title, if the differences between the subject matter sought to be patented and the prior art are such that the subject matter as a whole would have been obvious at the time the invention was made to a person having ordinary skill in the art to which said subject matter pertains. Patentability shall not be negatived by the manner in which the invention was made.

Claims 14 and 21 are rejected under 35 U.S.C. 103(a) as being unpatentable over Zhu, Patent No. 5,930,164 B1 – Date of Patent: Feb. 26, 1998 in view of Ohtani, Pub. Date: Mar. 18, 2004.

Regarding dependent claims 14 and 21, Zhu as applied to claims 11 and 18 above, disclose every aspect to applicant's claimed invention except for a second conductor connected to the second free layer; wherein the first conductor connects to the first free layer; and wherein the first and second magnetic junction devices can be simultaneously written to using the second and first conductors respectively.

Figs. 2 and 6 of Ohtani disclose a second conductor [PL] connected to the second free layer [18]; wherein the first conductor [PL] connects to the first free layer [18]; and wherein the first [13] and second [14] magnetic junction devices can be simultaneously written to using the second and first conductors [PL's] respectively (Page 4, paragraph [0046] lines 1-4).

Zhu and Ohtani are common subject matter for Magnetic Tunnel Junction.

Therefore it would have been obvious to one having ordinary skill in the art at the time the invention was made to incorporate Ohtani's conductor into the integrated circuit of Zhu for the purpose of performing the writing of signals to first and second tunneling magneto-resistance elements more rapidly (Abstract, lines 7-9).

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5. Claims 15 and 22 are rejected under 35 U.S.C. 103(a) as being unpatentable over Zhu, Patent No. 5,930,164 B1 – Date of Patent: Feb. 26, 1998 in view of Gill, Patent No.: US 6,185,080, Date of Patent: Feb. 6, 2001.

Regarding dependent claims 15 and 22, Zhu as applied to claims 11 and 18 above, disclose every aspect to applicant's claimed invention except for wherein at least one of the free layers includes a spacer sandwiched between two ferromagnetic layers and the spacer.

Fig. 13 of Gill discloses at least one of the free layers [205 or 235] includes a spacer [210 or 230] sandwiched between two ferromagnetic layers ([82 and 229] or [80 and 217], Col. 7 lines 35 and Col. 10 line 1-2).

Zhu and Gill are common subject matter for Magnetic Tunnel Junction. Therefore it would have been obvious to one having ordinary skill in the art at the time the invention was made to incorporate the free layers includes a spacer of Gill into the memory cell of Zhu for the purpose of increasing the effect of the sensor when the magnetic moment of the free layers rotate (Col. 2 lines 29-30).

6. Claim 23 is rejected under 35 U.S.C. 103(a) as being unpatentable over Zhu, Patent No. 5,930,164 B1 in view of Gill, Patent No.: US 6,185,080 and further view of Chen, Patent No.: US 6,469,926 B1 – Date of Patent: Oct. 22, 2002.

Regarding dependent claim 23, Zhu and Gill as applied to claims 22 above, discloses every aspect to applicant's claimed invention except for the spacer comprises a synthetic anti-ferromagnetic material.

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Fig. 3 of Chen discloses the spacer [50] comprises in a synthetic antiferromagnetic material (Col. 2 lines 66-67).

Zhu, Gill and Chen are common subject matter for Magnetic Tunnel Junction. Therefore it would have been obvious to one having ordinary skill in the art at the time the invention was made to incorporate Chen's synthetic anti-ferromagnetic material into Zhu and Gill's spacer for the purpose of improving magnetoresistance ratio and a decrease in voltage dependence (Abstract, lines 14-17).

#### Prior art

7. The prior art made of record and not relied upon is considered pertinent to applicant's disclosure.

Ho et al. Patent No.: US 7,020,009 B2 Date of Patent: Mar. 28, 2006

## **Contact Information**

8. Any inquiry concerning this communication from the examiner should be directed to Dang Nguyen, who can be reached by telephone at (571) 272-1955. Normal contact times are M-F, 8:00 AM - 4:30 PM.

Upon an unsuccessful attempt to contact the examiner, the examiner's supervisor, Richard Elms, may be reached at (571) 272-1869.

Any inquiry of a general nature or relating to the status of this application or proceeding should be directed to the receptionist, whose telephone number is (703) 305-3900. The faxed phone number for organization where this application or proceeding is assigned is (703) 872-9306.

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Information regarding the Status of an application may be obtained from the patent Application Information Retrieval (PAIR) system. Status information for published applications may be obtained from either Private PAIR or Public PAIR. Status information for unpublished applications is available through Private PAIR only. For more information about the PAIR system, see http://pair-direct.uspto.gov. Should you have questions on access to the Private PAIR system, contact the Electronic Business Center (EBC) at 866-217-9197 (toll-free) or EBC@uspto.gov.

Dang Nguyen 07/15/2006

RICHARD ELMS

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